

INFORMATION DISCLOSURE STATEMENT

BY APPLICANT

Docket: 6047-53173

App: 09/590,795

Applicant: Vishnu K. Agarwal et al.

Filed: June 8, 2000

Art Unit:

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SEP 15 2000

TECHNOLOGY CENTER 2800

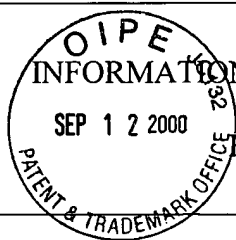
U.S. PATENT DOCUMENTS

Init.*		Number	Date	Name	Class	Sub	Filed
DV		6,060,367 ✓	5/9/00	Sze			
		6,060,351 ✓	5/9/00	Parekh et al.			
		6,049,101 ✓	4/11/00	Graettinger et al.			
		6,037,220 ✓	3/14/00	Chien et al.			
		6,015,743 ✓	1/18/00	Zahurak et al.			
		5,962,065 ✓	10/5/99	Weimer et al.			
		5,985,714 ✓	11/16/99	Sandhu et al.			
		5,959,327 ✓	9/28/99	Sandhu et al.			
		5,877,063 ✓	3/2/99	Gilchrist			
		5,696,014 ✓	12/9/97	Figura			
		5,612,560 ✓	3/18/97	Chivukula et al.			
		5,608,247 ✓	3/4/97	Brown			
		5,427,974 ✓	6/27/95	Lur et al.			
		5,372,962 ✓	12/13/94	Hirota et al.			
		5,342,800 ✓	8/30/94	Jun			
DV		5,318,920 ✓	6/7/94	Hayashide			

EXAMINER: *Bhuland*

DATE *09/27/01*

*Examiner: Initial if considered, whether or not in conformance with MPEP 60; draw line through cite if not in conformance and not considered. Send copy.



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SEP 12 2000

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Init.*		Number	Date	Name	Class	Sub	Filed
DV		5,130,885✓	7/14/92	Fazan et al.			
DV		5,068,199✓	11/26/91	Sandhu			

FOREIGN PATENT DOCUMENTS

		Number	Date	Country	Class	Sub	

OTHER DOCUMENTS

DV			Kawahara, Takaaki et al., "(Ba, Sr)TiO ₃ Films Prepared by Liquid Source Chemical Vapor Deposition on Ru Electrodes," <u>Jpn. J. Appl. Phys.</u> , 35:4880-4885 (1996).

EXAMINER:

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